

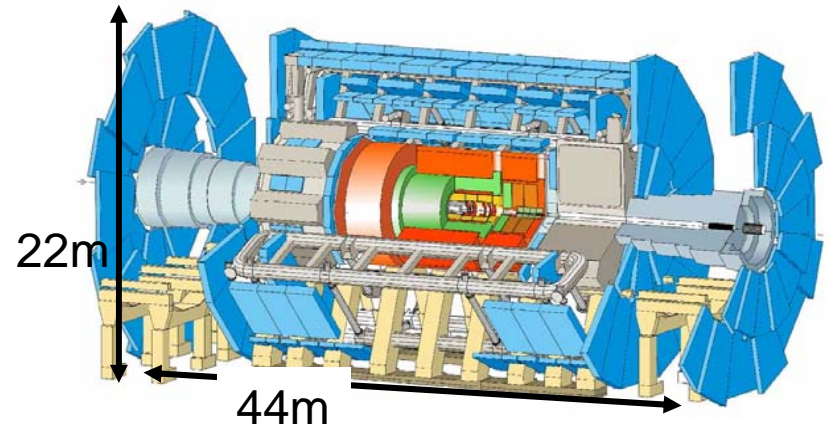
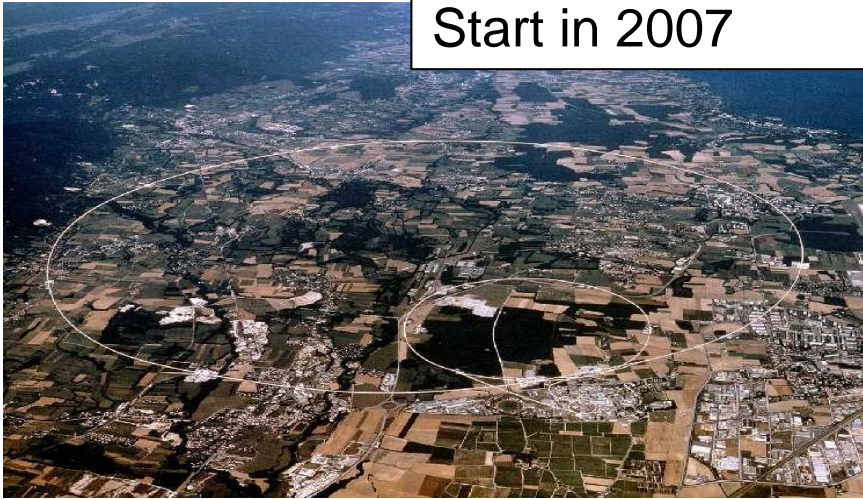
Upgrade of ATLAS silicon semiconductor tracker for the SLHC

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Koki Inoue

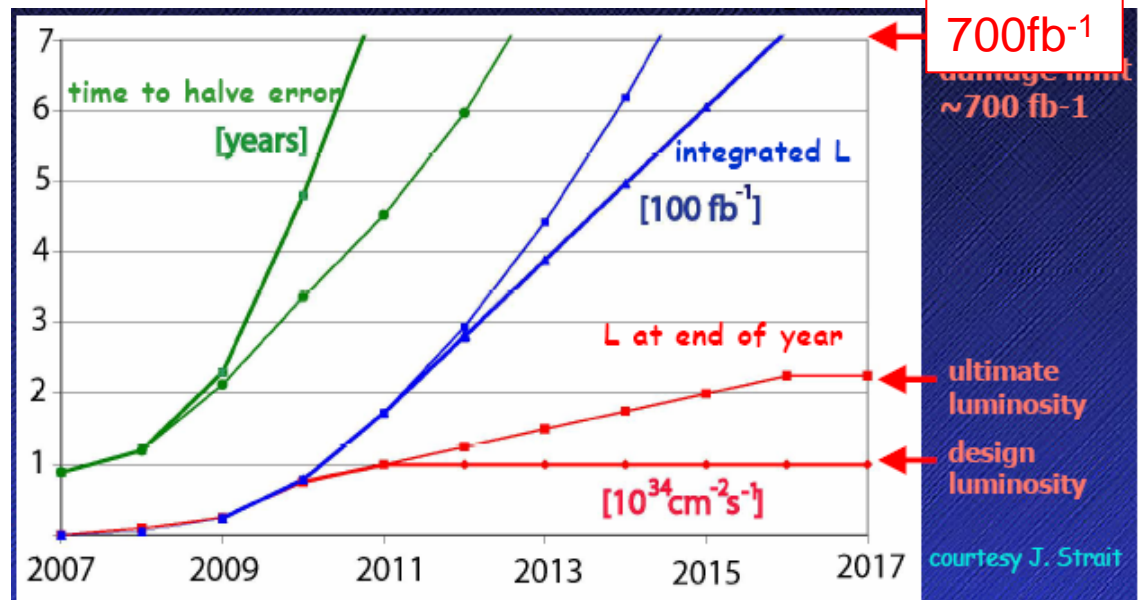
1. LHC experiment and ATLAS detector
2. super LHC
3. P-bulk test samples and irradiation
4. IV, CV/CCE, isolation measurement results
5. Summary

LHC experiment and ATLAS detector

Start in 2007

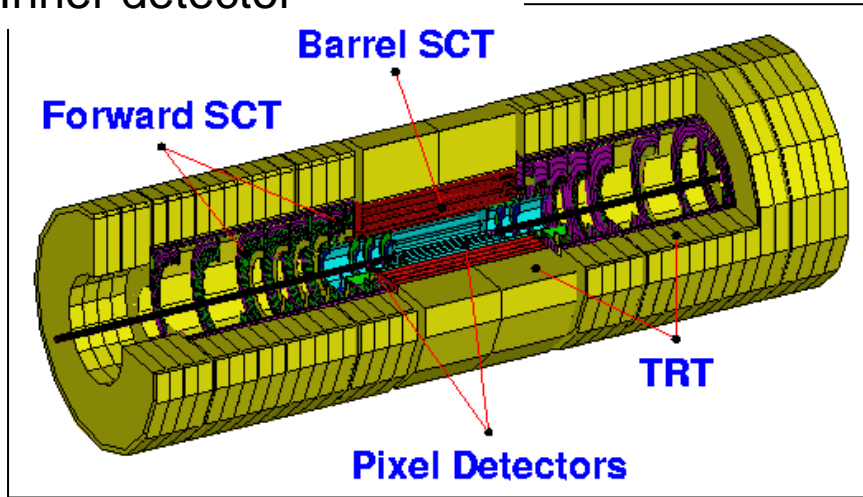


- Proton-Proton collider
- CM energy : 14 TeV
- Luminosity : $10^{34} \text{ cm}^{-2}\text{s}^{-1}$
- Collision interval : 25 nsec
- 700 fb^{-1} by 2014~2016



Inner detector and semiconductor tracker

Inner detector



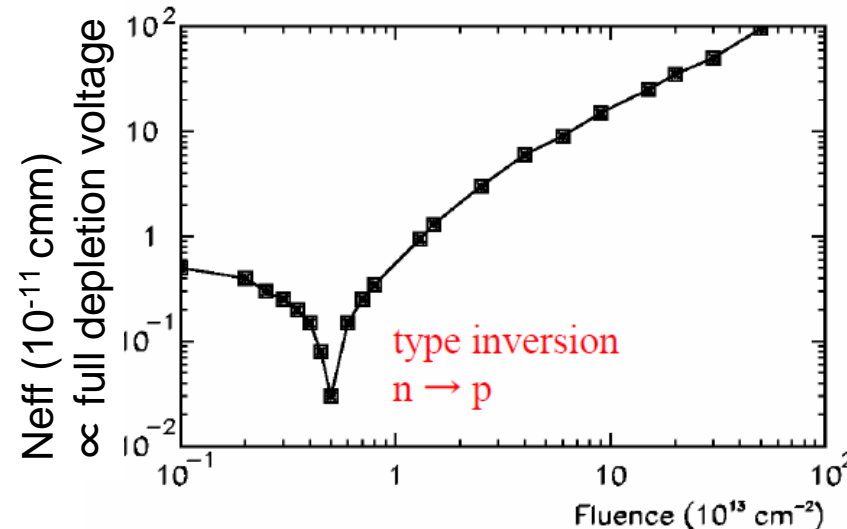
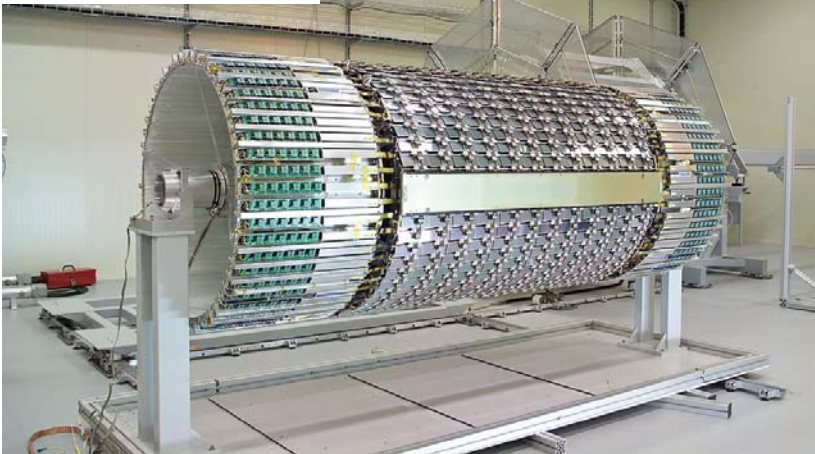
SCT Radiation tolerance

$\sim < 2 \times 10^{14} (1 \text{ MeV-n-eq/cm}^2)$
(10 years of LHC experiment)

SCT property

- N-type sensor
 - be fully depleted for signal readout
- With fluence, full depletion voltage increase.
- Operation Voltage limits the lifetime

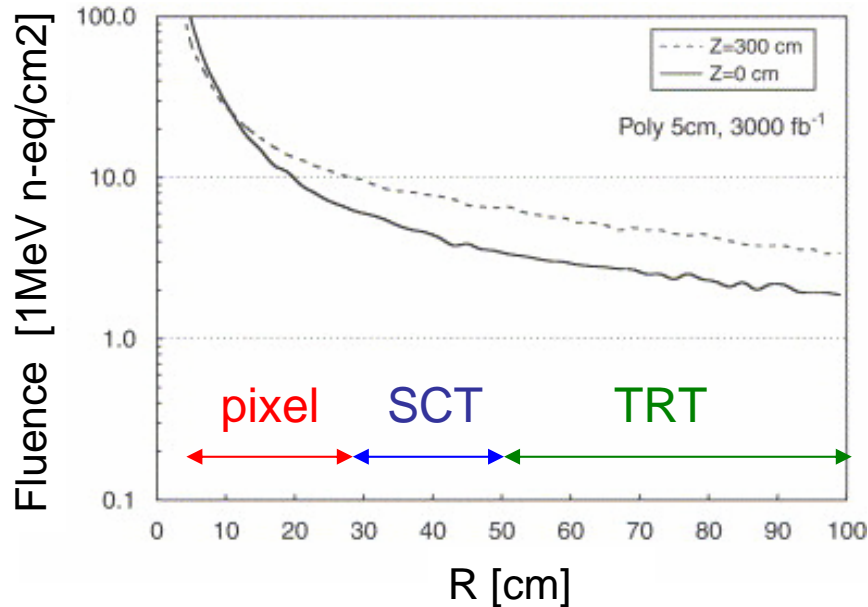
Barrel SCT



Super-LHC

SLHC parameters

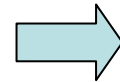
- Luminosity : 10^{35} /cm²/s
- Integrated luminosity : 3000 fb⁻¹
- Collision interval : 12.5 ns
- Particle fluence



$\sim 1 \times 10^{15}$ (1MeV n-eq/cm²) @R=30 cm

ATLAS Inner Detector needs re-designed

- Replace TRT with silicon detector
- Need more rad-hard silicon detector



Developing P-type sensor

Advantage of N⁺-on-P sensor:

✓ Signal can be accumulated even under partial depletion (operational at reduced HV).

R&D goals:

✓ evaluate high resistive p-type wafers → stability against radiation

✓ electrical isolation between N⁺ readout strips.

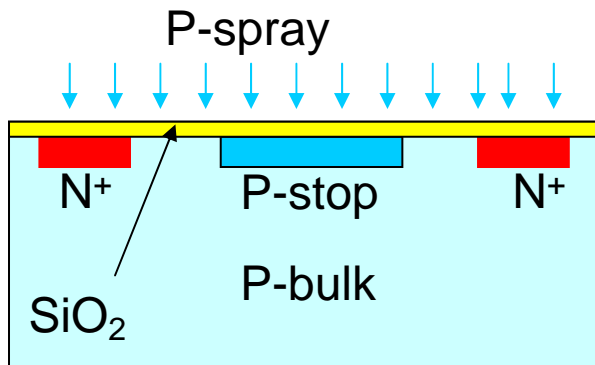
P-bulk test Samples for rad-hard silicon

40 samples

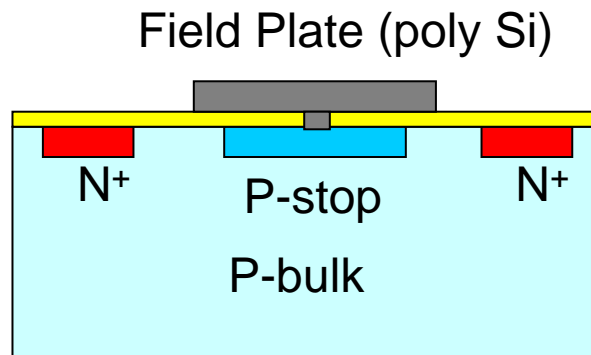
- wafer types: Floating Zone (FZ), Magnetic Czochralski (MCZ) → Next page
- 5 p-stop structures
(IPSTP, CPSTP, IPSTPDF, CPSTPDF, AF)
- 2 p-stop/p-spray concentrations
- 2 fluences

concentrations

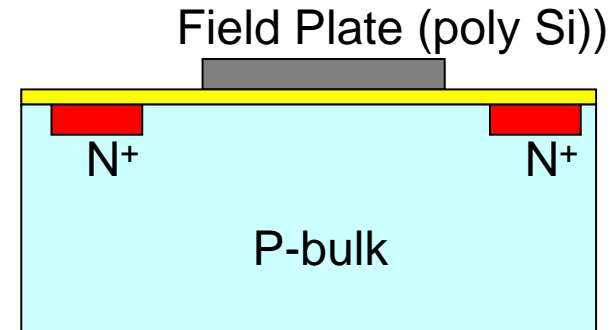
wafer No	p-stop	p-spray
7,8	1E+12	1E+12
17,18	2E+13	---



P-stop (Common, Individ.)



P-stop + DC Field Plate
(Common, Individ.)



AC Field Plate

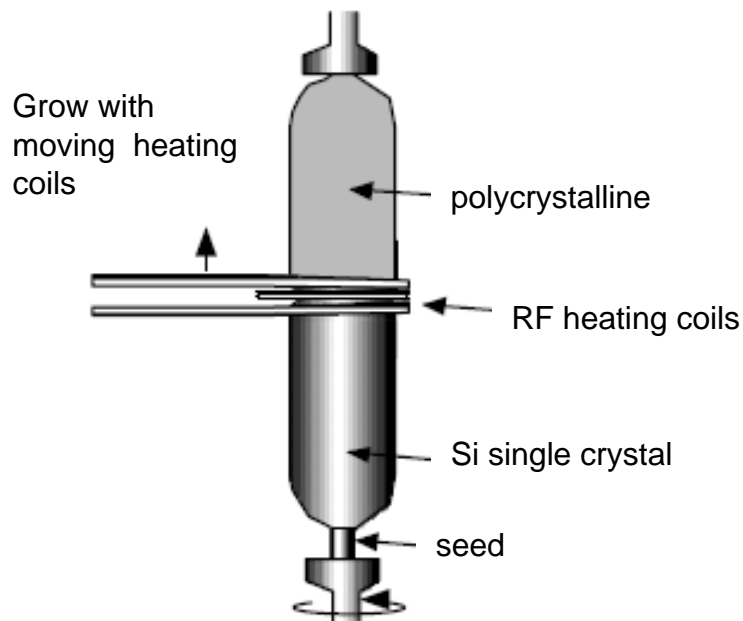
wafer 7/17: irradiated to 0.7×10^{14} /cm² (low fluence)

wafer 8/18: irradiated to 0.7×10^{15} /cm² (high fluence)

P-bulk test Samples for rad-hard silicon

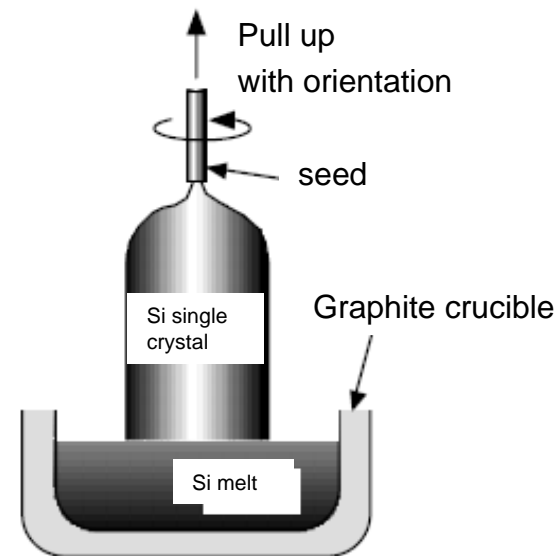
Floating Zone (FZ) crystal growth

- Resistivity $\sim 1.5\text{k } \Omega \cdot \text{cm}$
- Very low impurity



Magnetic Czochralski (MCZ) crystal growth

- Resistivity $\sim 1\text{k } \Omega \cdot \text{cm}$
- Oxide rich
(expected to decrease full depletion voltage for any irradiation)

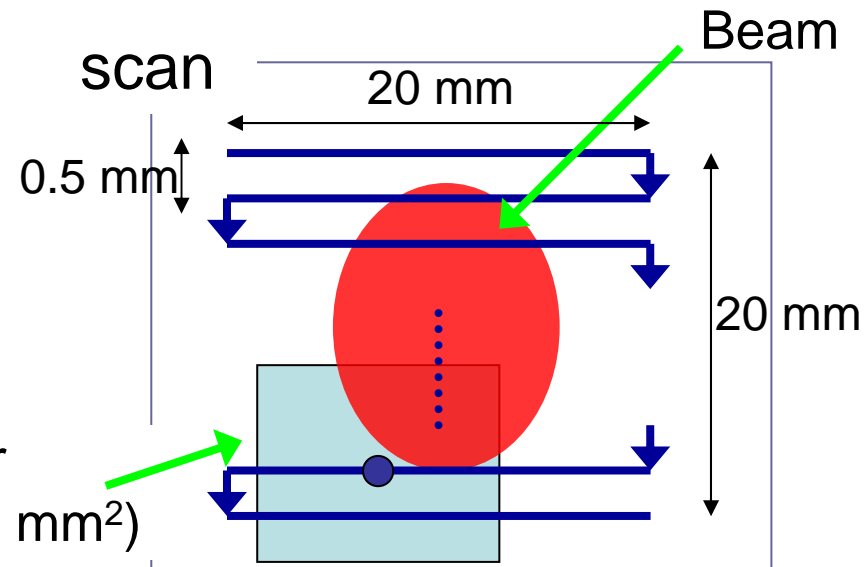
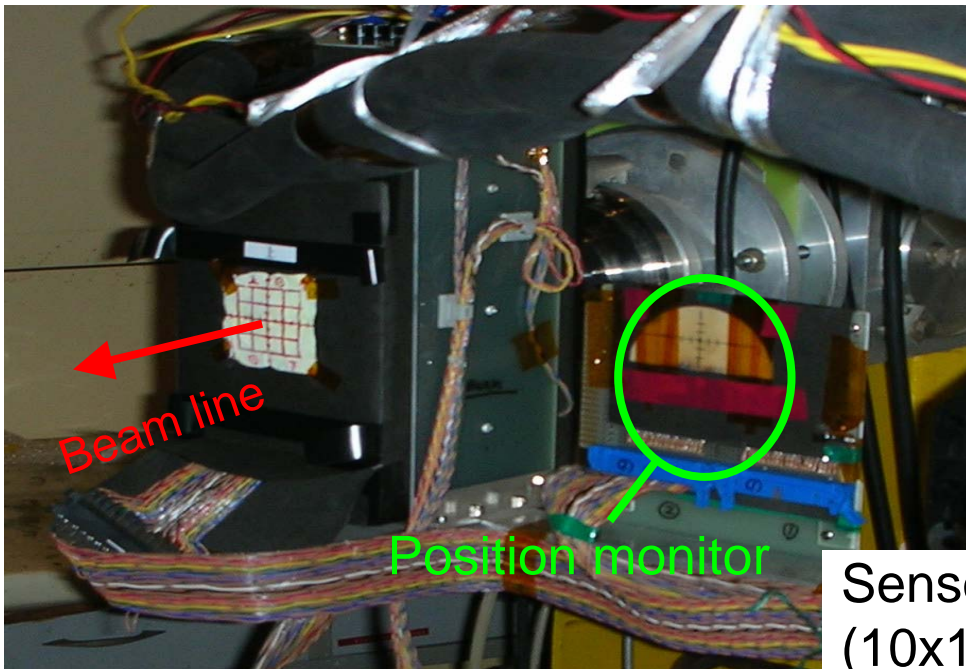
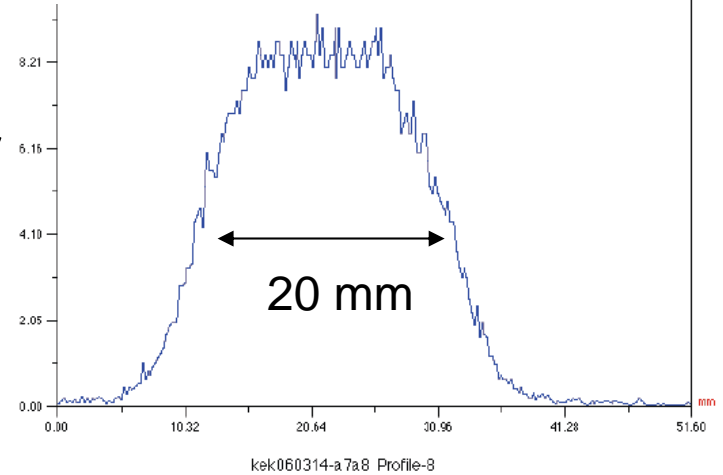


Full depletion voltage/Micro discharge/Strip isolation are compared for FZ and MCZ samples.

Irradiation@Tohoku Univ. CYRIC

- 70MeV protons
- center position determined by position monitor
- Irradiate evenly by scanning the sensors
- Fluence evaluated by AI activation

Beam profile

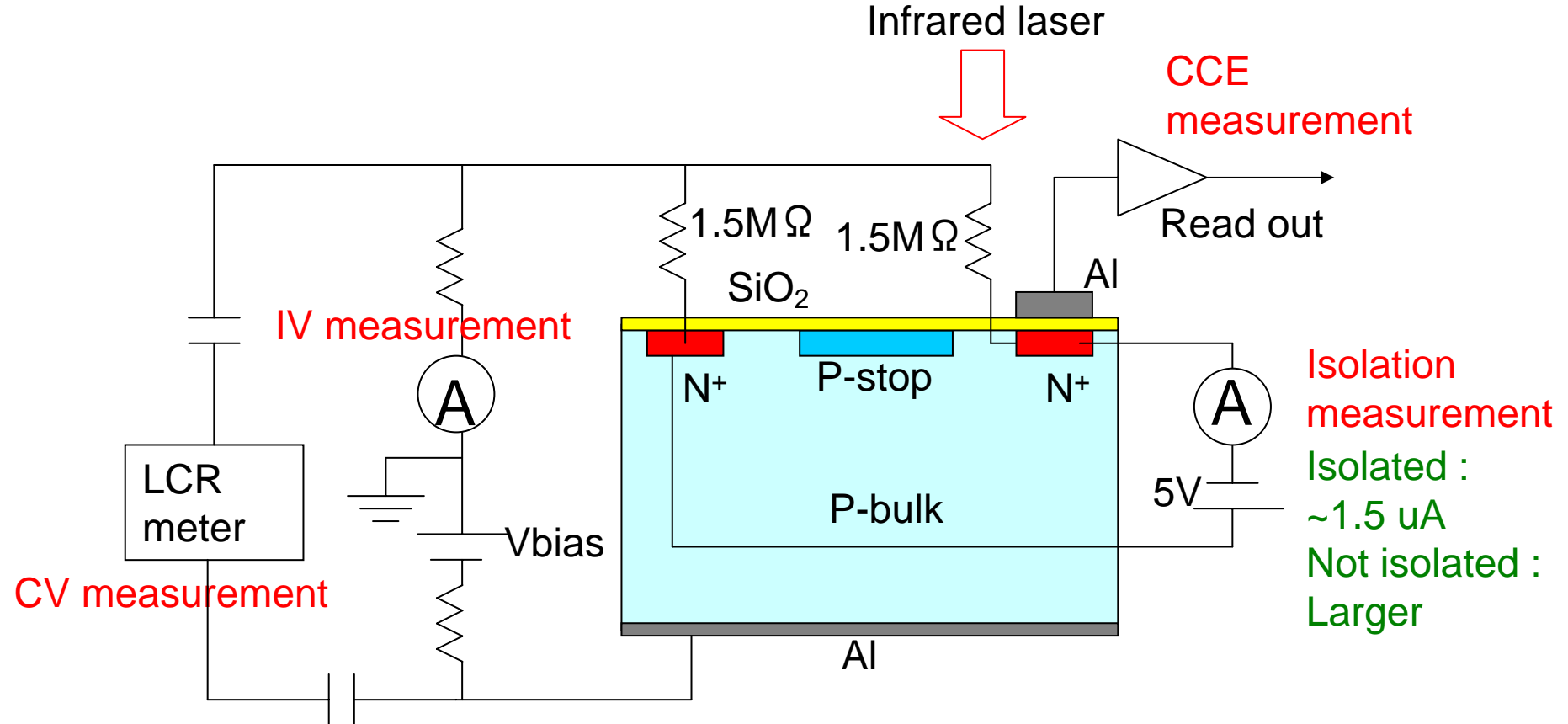


Measurements of sensor characteristics

I-V ... micro discharge ?

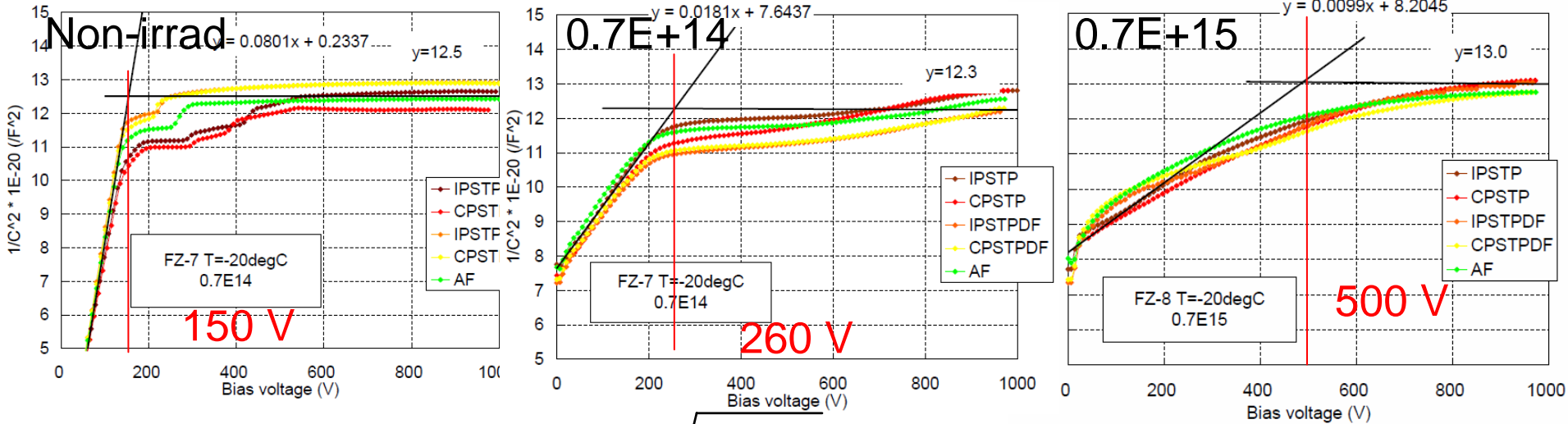
C-V/ CCE (Charge Collection Efficiency) ... evaluate full depletion voltage

Isolation ... evaluate electrical isolation between readout strips

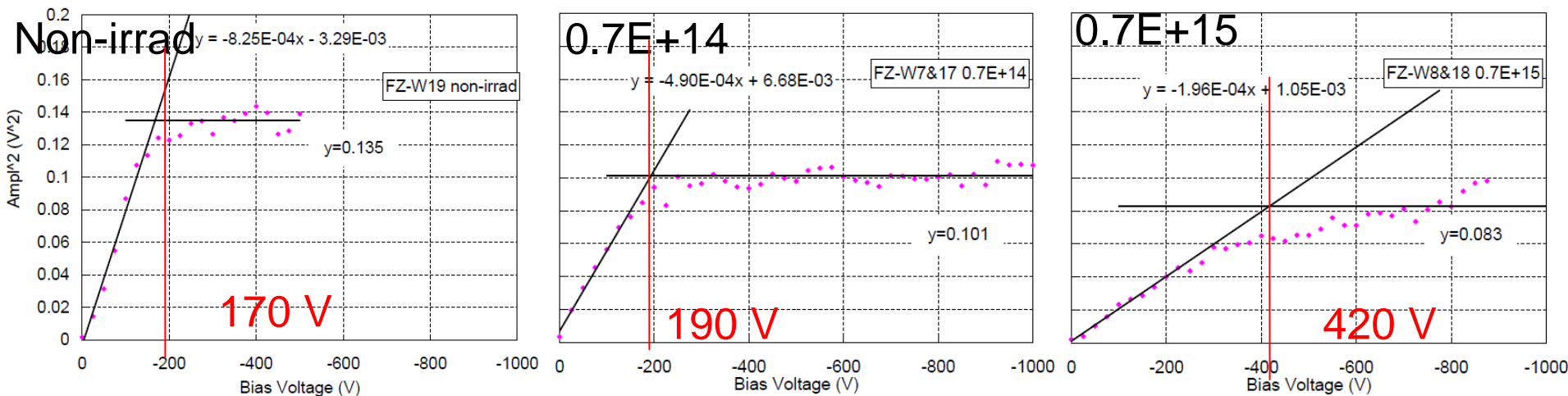


Full depletion voltage (FZ)

C-V $1/C^2$: plot $1/C \propto d \propto \sqrt{V_{bias}}$

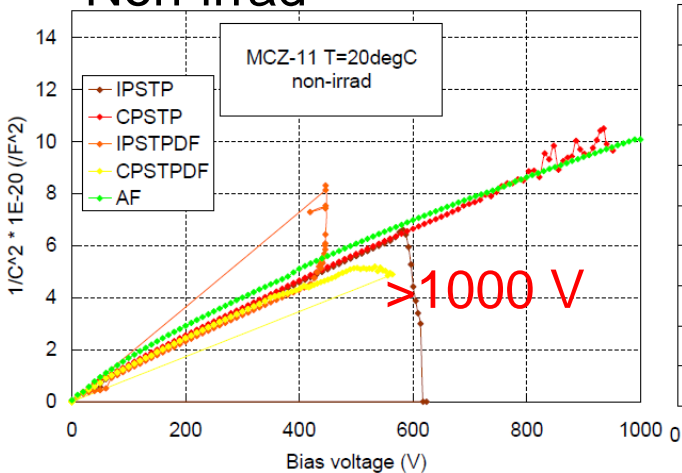


CCE : $ampl^2$ plot $ampl \propto d \propto \sqrt{V_{bias}}$

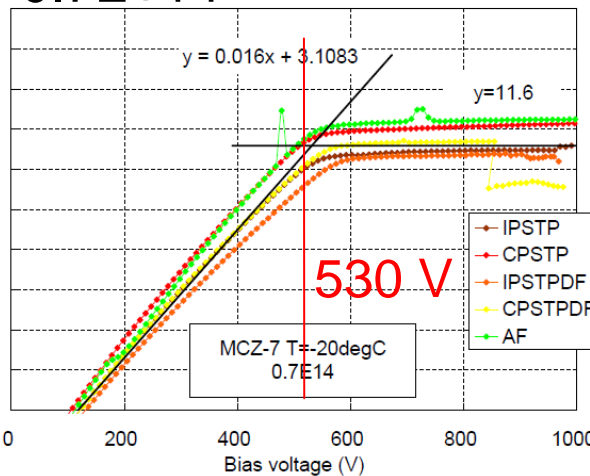


Full depletion voltage (MCZ)

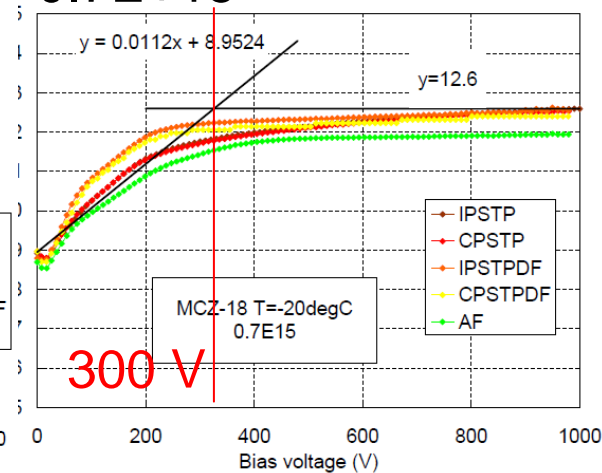
Non-irrad



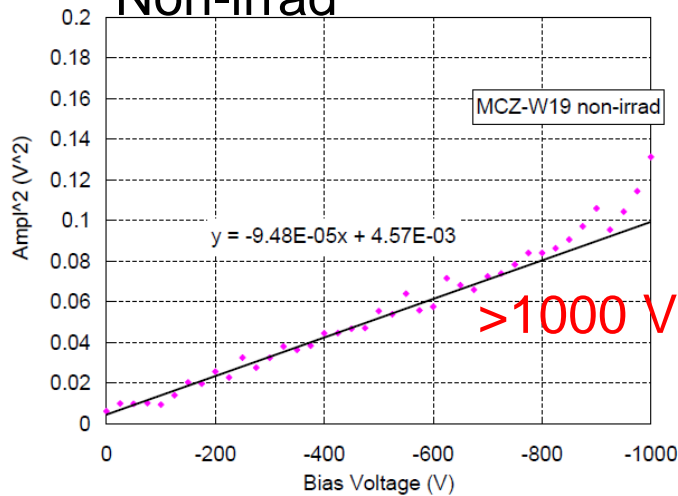
0.7E+14



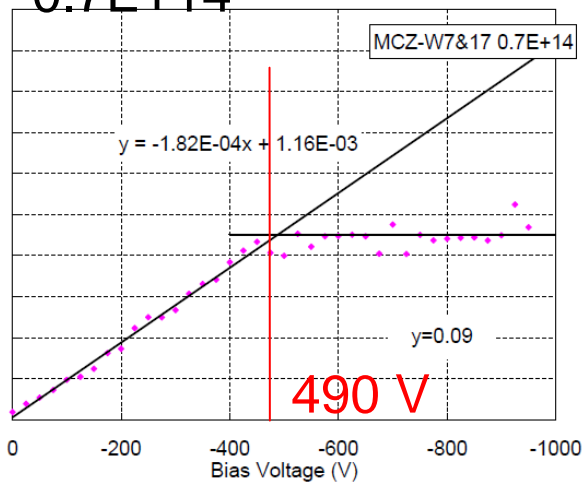
0.7E+15



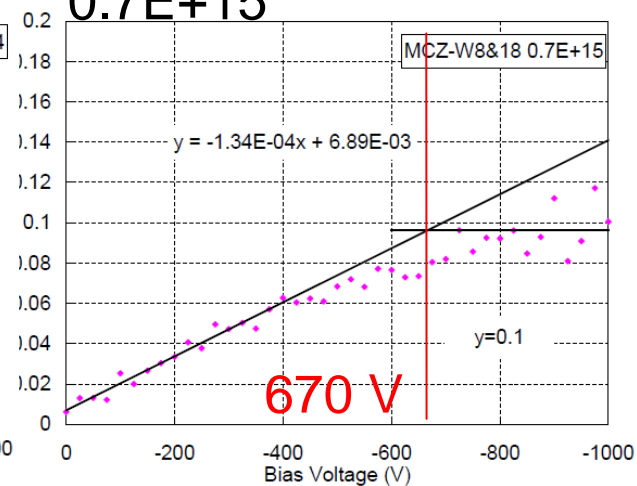
Non-irrad



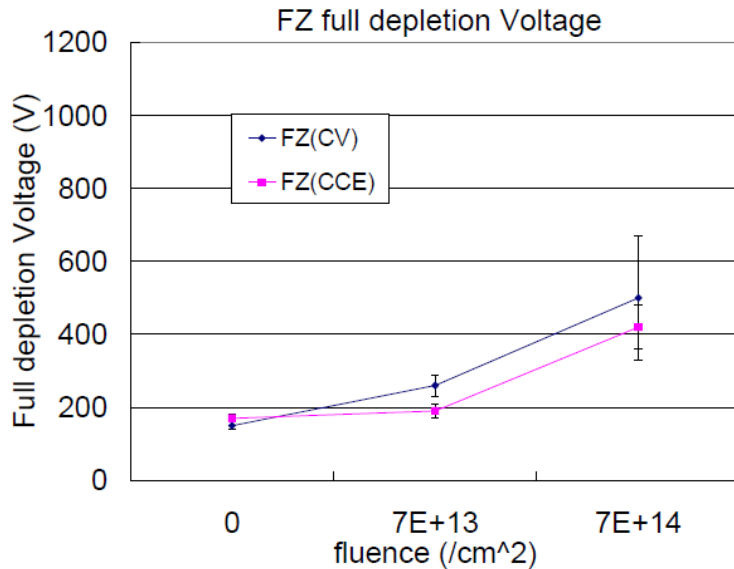
0.7E+14



0.7E+15



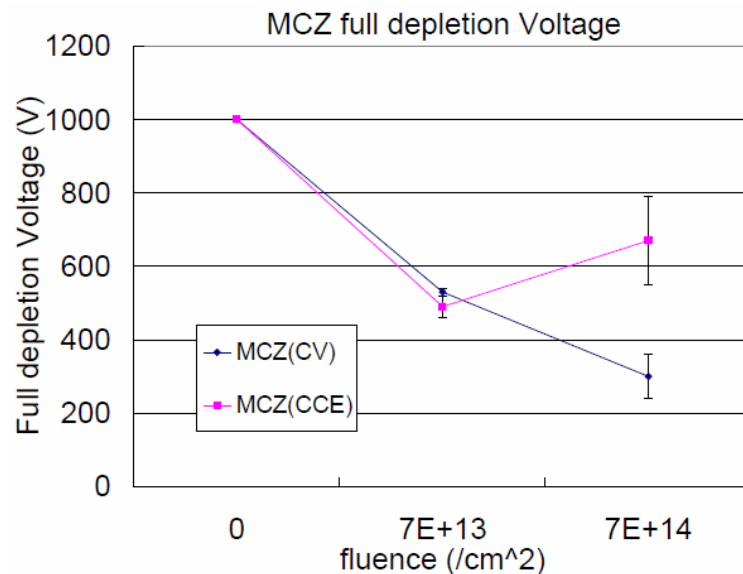
Full depletion voltage dependence on fluence



➤ FZ

~150 V before irradiation

Increases to ~500V after 0.7E+15



➤ MCZ

~1kV before irradiation

Decreases to ~500 V after 0.7E+13

Vfd after 0.7E+15 ?

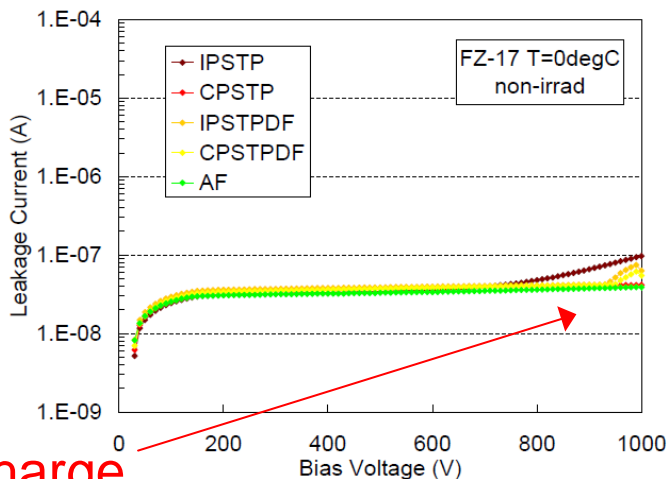
We have conducted more systematic irradiation:

Data to be ready in a month.

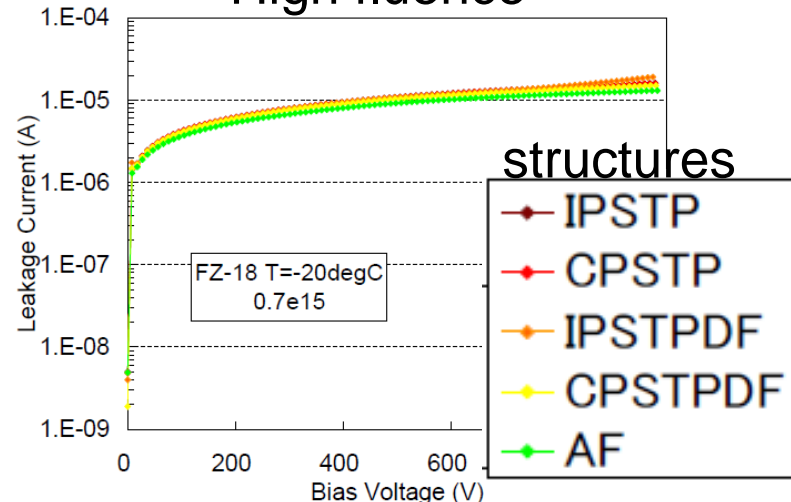
I-V Curve before/after irradiation

FZ

Non-irrad

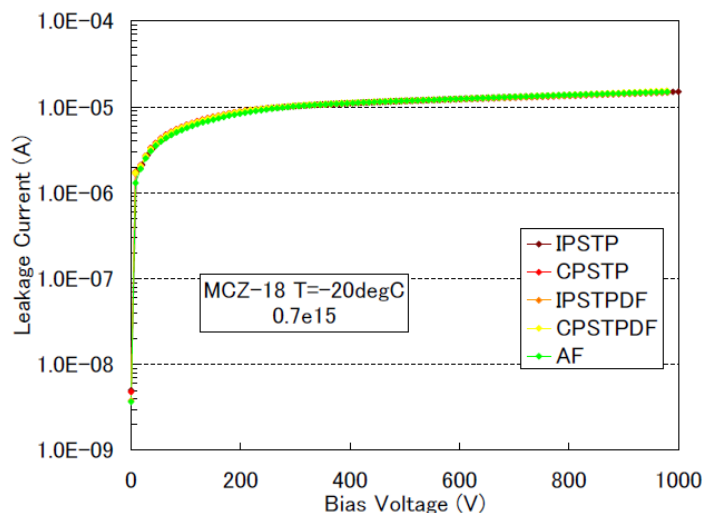
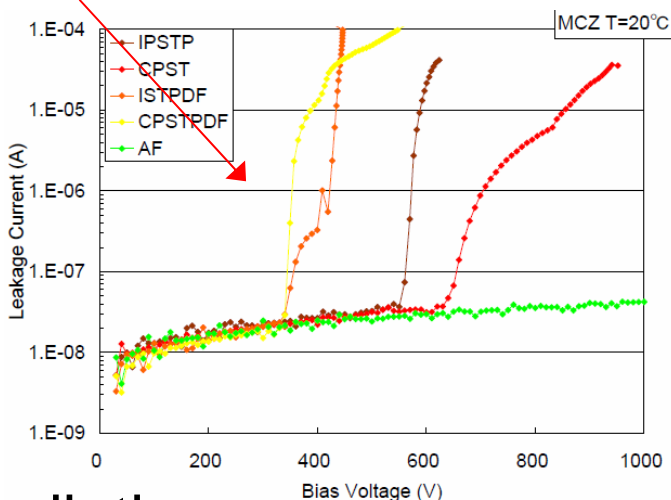


High fluence



Micro discharge

MCZ



After irradiation,

micro discharge disappears.

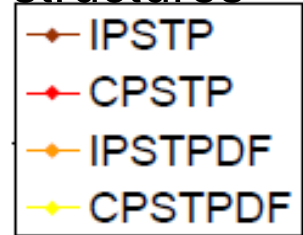
current is about 10 uA at T= -20°C (1 cm² sensor).

Strip Isolation of FZ

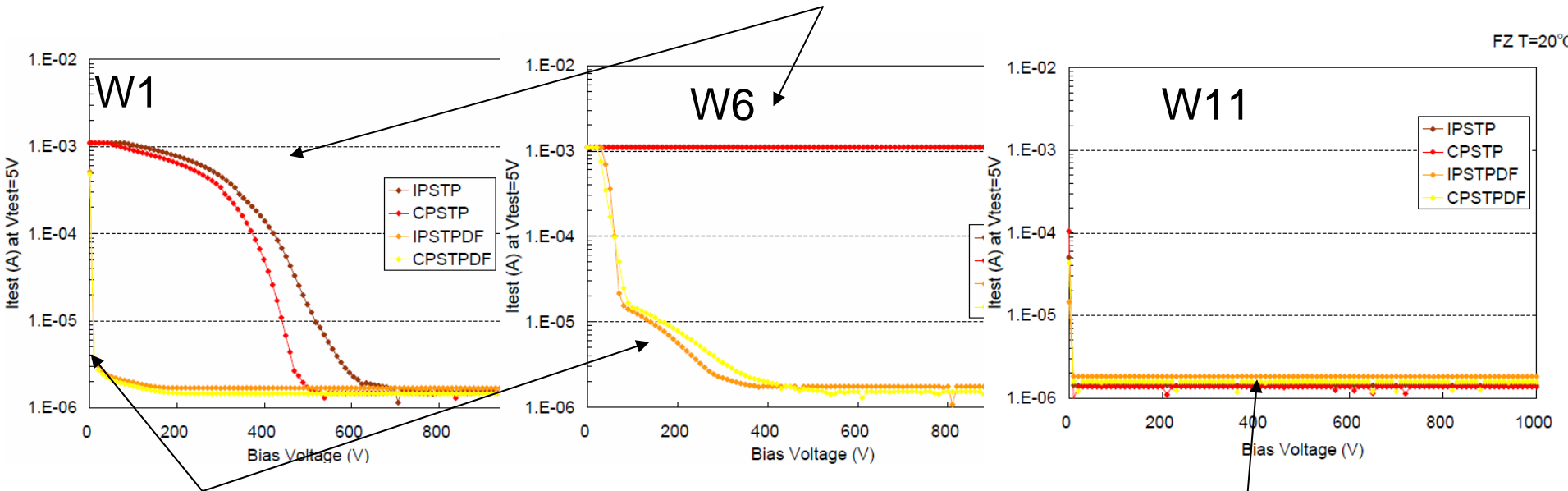
dependence on p-stop concentration (before irradiation)

wafer No	p-stop	p-spray
1	2E+12	2E+12
6	5E+12	---
11	2E+13	---

structures



with P-spray is better than without.



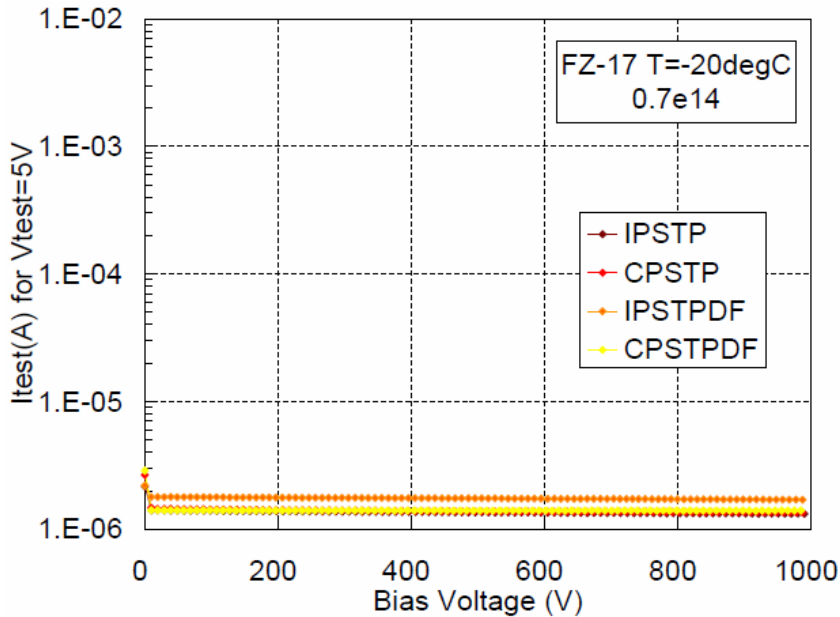
P-stop with DC Field Plates is better than without.

Need ~2E+13 p-stop (W11) to isolate (concentrations for W1/6 are not enough)

Strip Isolation of FZ

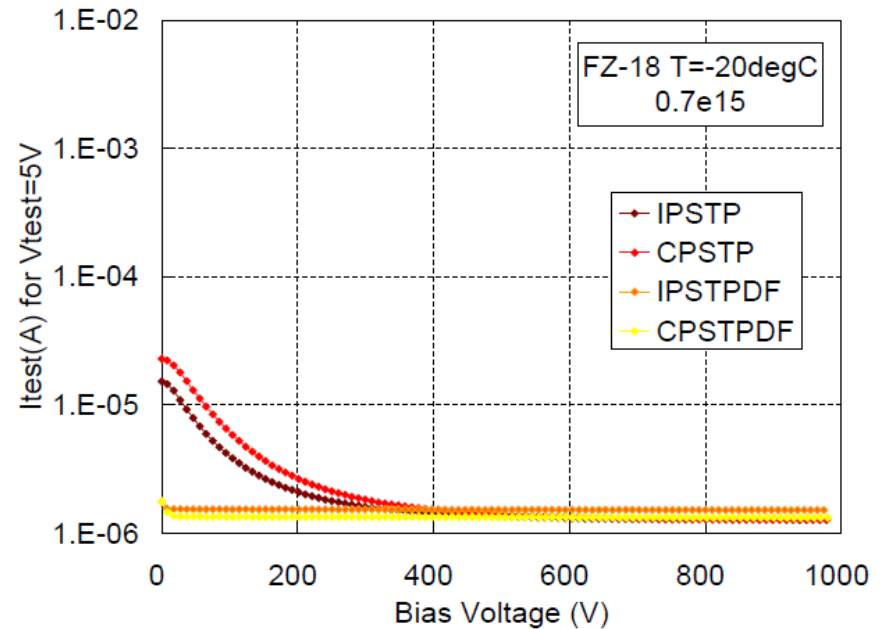
after irradiation (P-stop concentration: $2E+13$)

Low fluence



At low fluence,
isolation is still good.

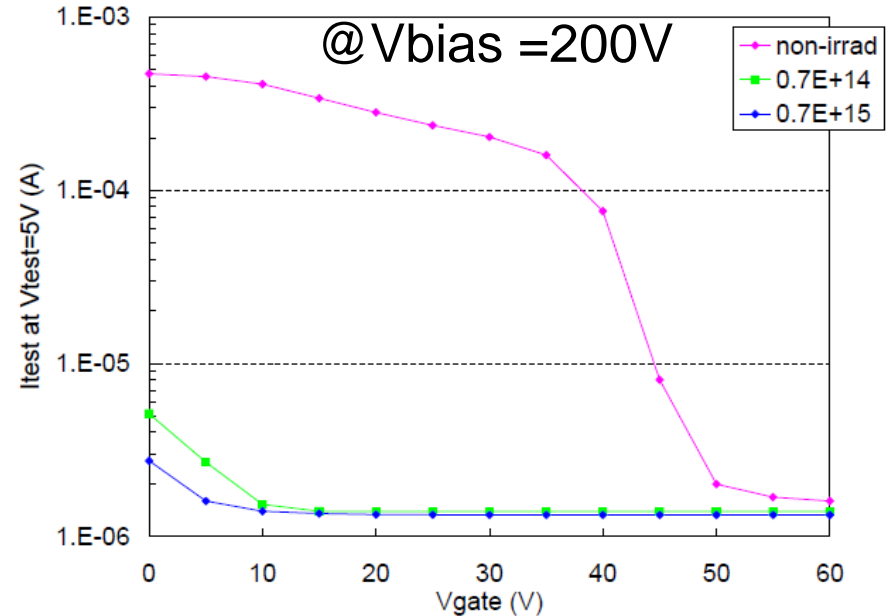
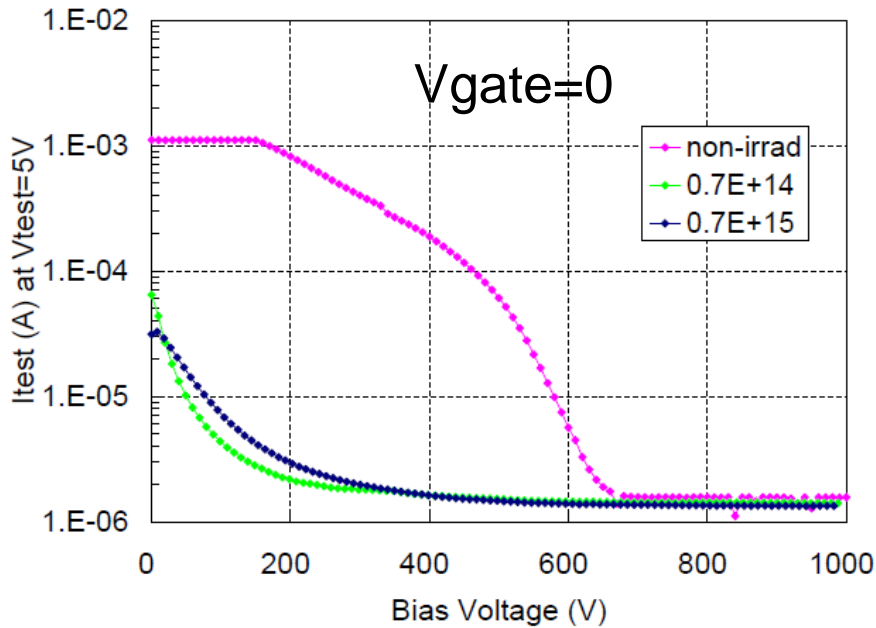
High fluence



At high fluence,
IPSTP/CSTP becomes worse.
DC field plate remains OK.

Strip Isolation of FZ

effectiveness of AC Field Plate



AF samples are not isolated at $V_{gate}=0$ and
HV below $\sim 650V$ (non-irrad)
HV below $\sim 300V$ (irradiated)

Isolation is achieved at
 $V_{gate} \sim -50V$ (non-irrad)
 $\sim -10V$ (irradiated)

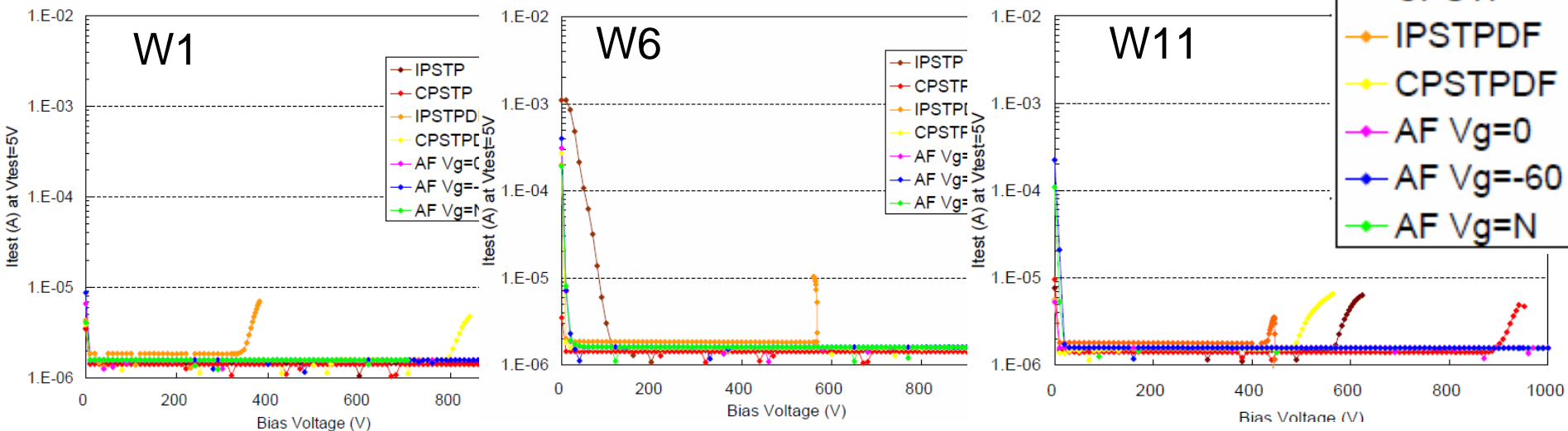
irradiation relaxes the isolation conditions

Strip Isolation of MCZ

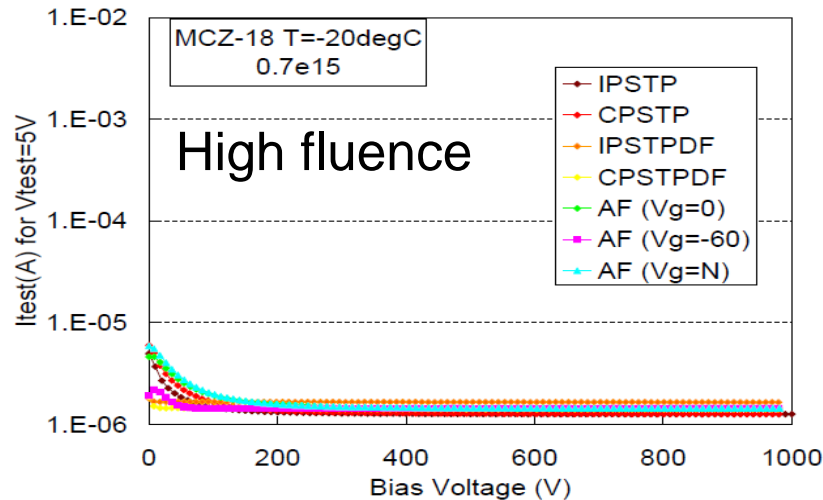
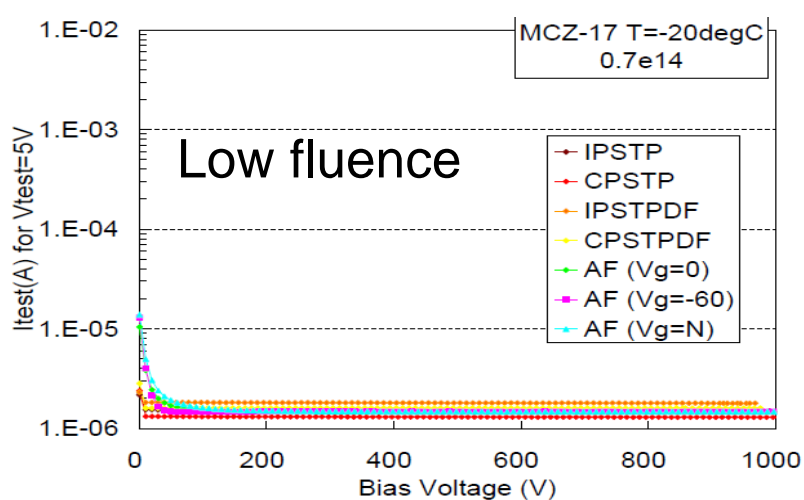
(before irradiation)

structures

- IPSTP
- CPSTP
- IPSTPDF
- CPSTPDF
- AF $V_g=0$
- AF $V_g=-60$
- AF $V_g=N$



MCZ samples are all OK. Also for AC Field Plate with $V_{gate}=0$



Summary

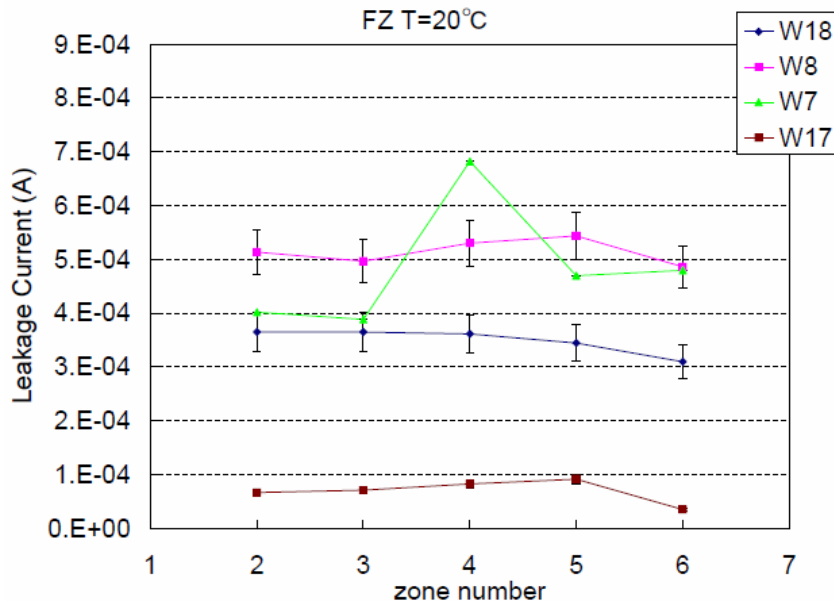
- We have been developing radiation tolerant silicon sensors for the SLHC.
- MCZ wafer is better at present data.

Wafer type	Full depletion voltage	Micro discharge	Strip isolation
FZ	~150 V (non-irrad) ~500 V (0.7E+15)	At 800 V (non-irrad)	•Need 2E+13 P-stop concentration •AC Field Voltage = -50 V
MCZ	~1k V (non-irrad) ~500 V (0.7E+14) to be re-evaluated (0.7E+15)	At 400 V (non-irrad)	All samples are good

- We have new data, covering fluence of 5E15 with 6 fluence points

Back up

Leakage Current @ Vfd



Leakage current are,

For FZ,

$$I_{leak_{18}} = 3.5 \times 10^{-4} \pm 5 \% A$$

$$I_{leak_{8}} = 5.1 \times 10^{-4} \pm 8 \% A$$

$$I_{leak_{17}} = 0.69 \times 10^{-4} \pm 15 \% A$$

$$I_{leak_{7}} = 4.8 \times 10^{-4} \pm 12 \% A$$

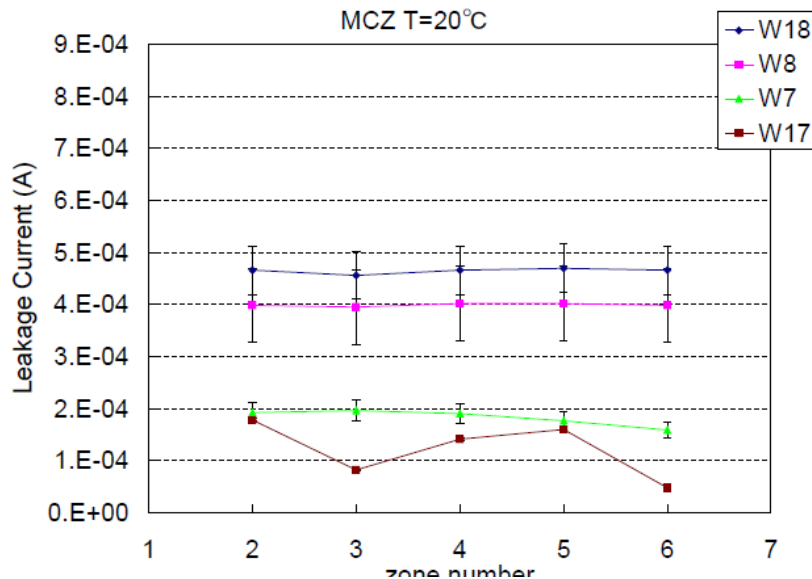
For MCZ

$$I_{leak_{18}} = 4.7 \times 10^{-4} \pm 5 \% A$$

$$I_{leak_{8}} = 4.0 \times 10^{-4} \pm 4 \% A$$

$$I_{leak_{17}} = 1.8 \times 10^{-4} \pm 20 \% A$$

$$I_{leak_{7}} = 1.2 \times 10^{-4} \pm 6 \% A$$



Damage constant

$$\frac{\Delta I}{Volume} = \alpha \Phi$$

Damage constant α are,

For FZ,

$$\alpha_{18} = 1.7 \times 10^{-17} \pm 5 \% \text{ (A/cm)}$$

$$\alpha_8 = 2.5 \times 10^{-17} \pm 8 \% \text{ (A/cm)}$$

$$\alpha_{17} = 3.3 \times 10^{-17} \pm 15 \% \text{ (A/cm)}$$

$$\alpha_7 = 23 \times 10^{-17} \pm 10 \% \text{ (A/cm)}$$

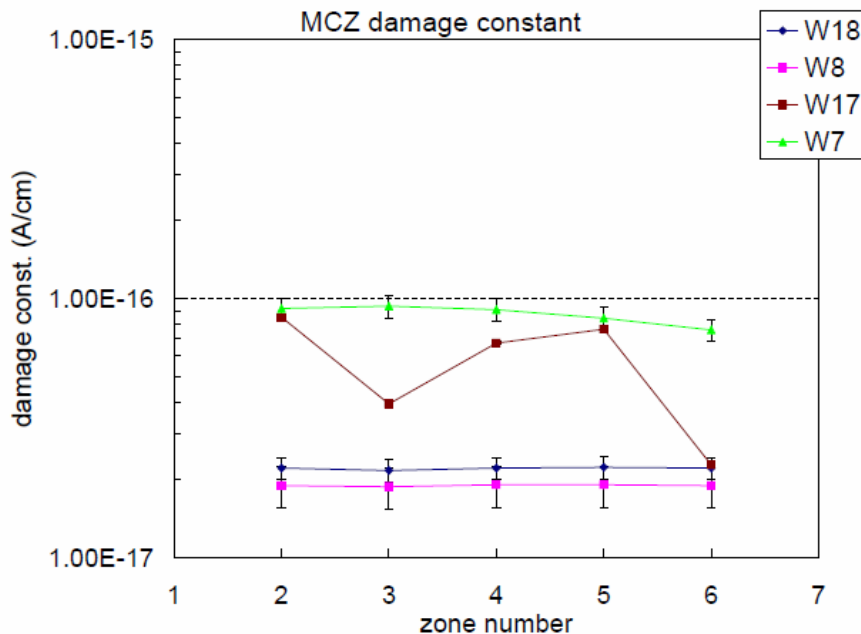
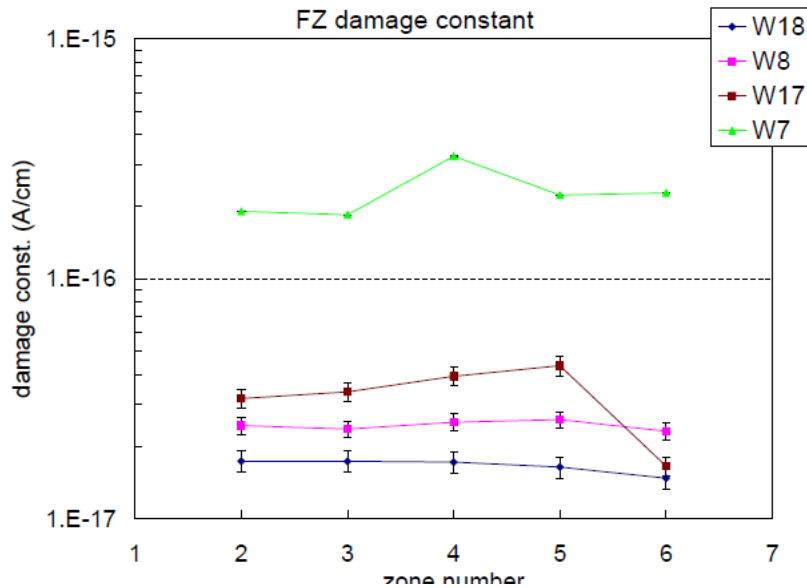
For MCZ,

$$\alpha_{18} = 2.2 \times 10^{-17} \pm 5 \% \text{ (A/cm)}$$

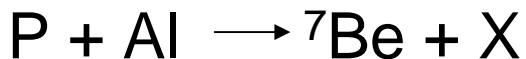
$$\alpha_8 = 1.9 \times 10^{-17} \pm 5 \% \text{ (A/cm)}$$

$$\alpha_{17} = 5.8 \times 10^{-17} \pm 20 \% \text{ (A/cm)}$$

$$\alpha_7 = 8.7 \times 10^{-16} \pm 5 \% \text{ (A/cm)}$$



Fluence evaluation from Al activation



$$\Phi \cong \frac{N_{mes} \exp(\lambda \Delta t)}{N_t \sigma \lambda E_{eff} \Gamma}$$

N_{mes} : # of γ per second

λ : ${}^7\text{Be} \rightarrow \gamma$ (477KeV)
decay rate

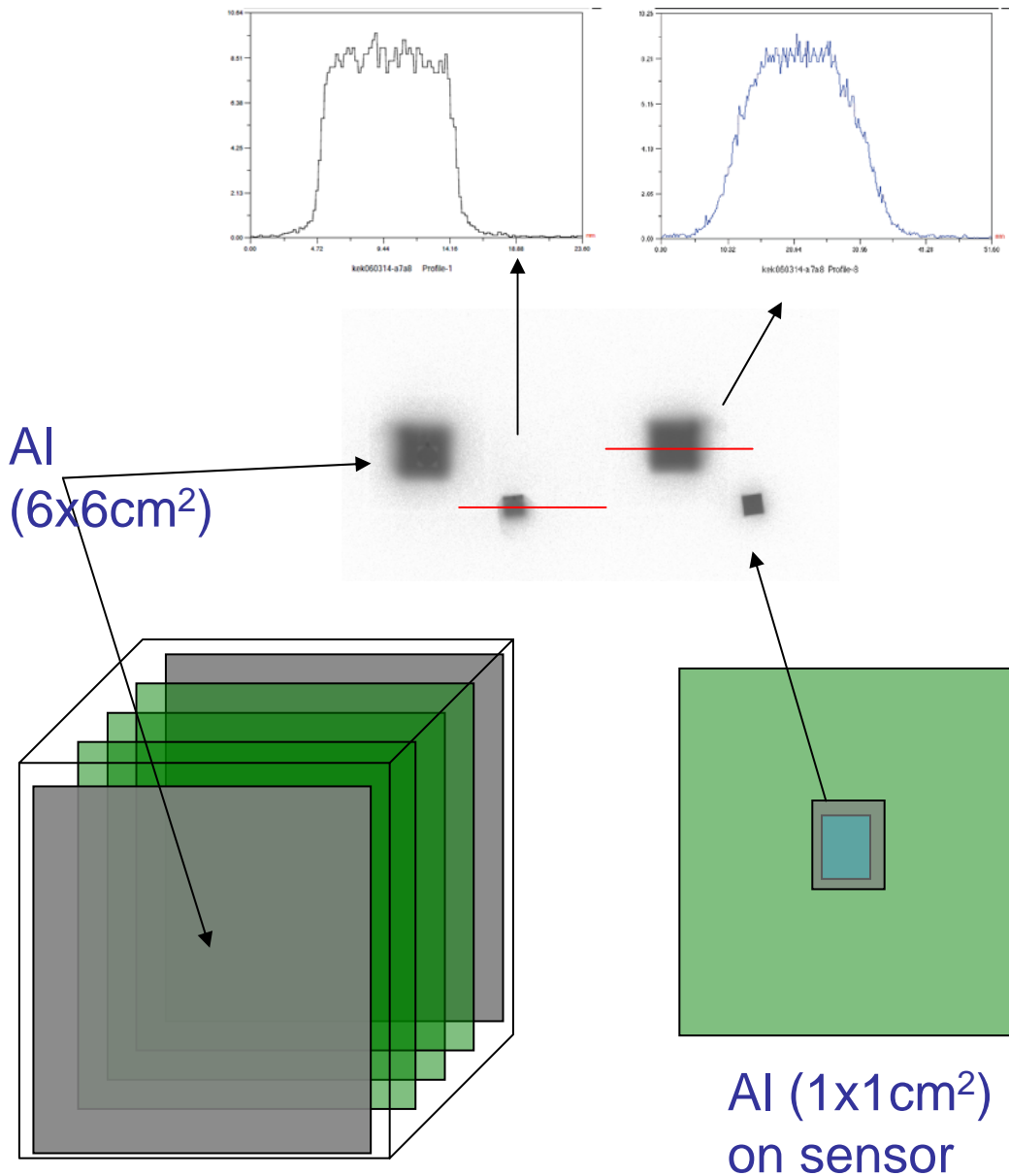
Δt : time from beam off to
measurement

N_t : # of Al atom

Γ : ${}^7\text{Be} \rightarrow \gamma$ (477KeV)
Branching ratio

σ : cross section

E_{eff} : SSD efficiency



Silicon detector and laser

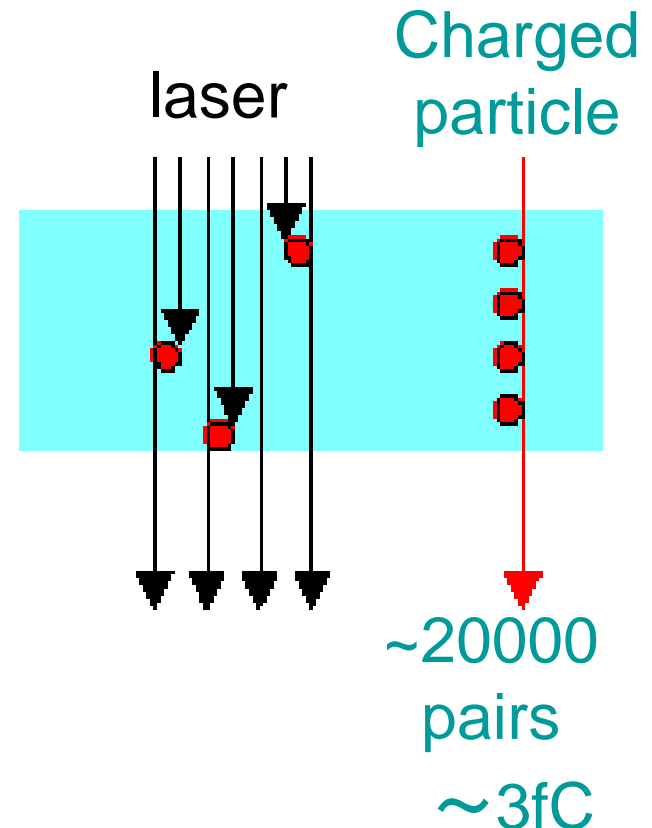
The laser in this measurement is solid-state laser which cavity is YAG (yttrium, aluminum, garnet) crystal doped Nd (neodymium).

1064nm laser is emitted by excitation and transition of Nd^{3+} ion.

Nd:YAG laser	1064nm=1.16eV
Silicon energy gap	=1.12eV



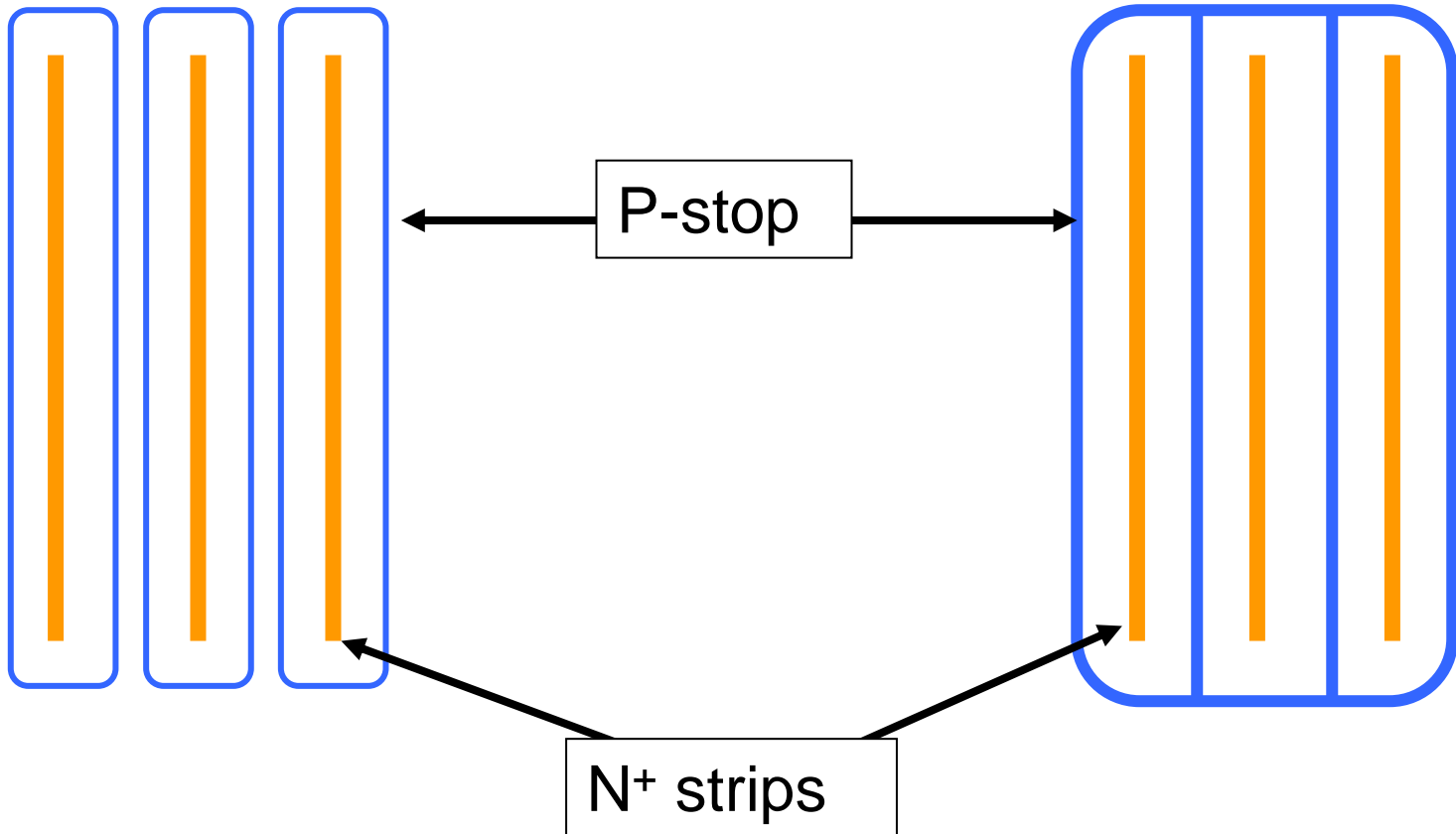
- Although almost laser pass through the silicon, can create electron-hole pair in a probability. Evenly for the silicon depth.
 - Can control number of creation by adjusting light quantity.



P-stop shape

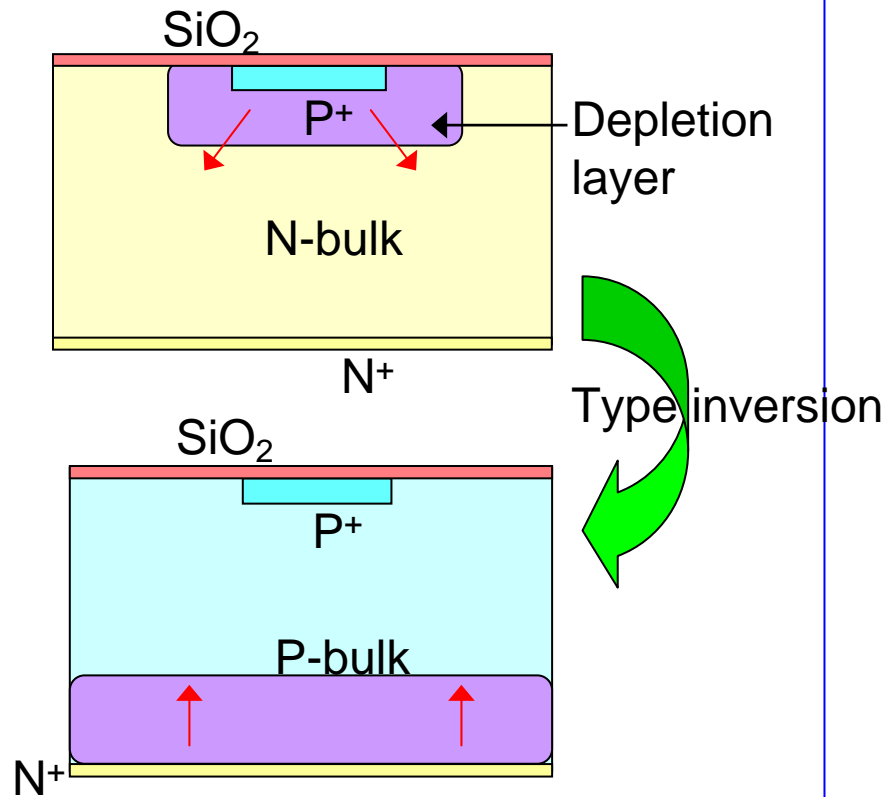
Individual

Common

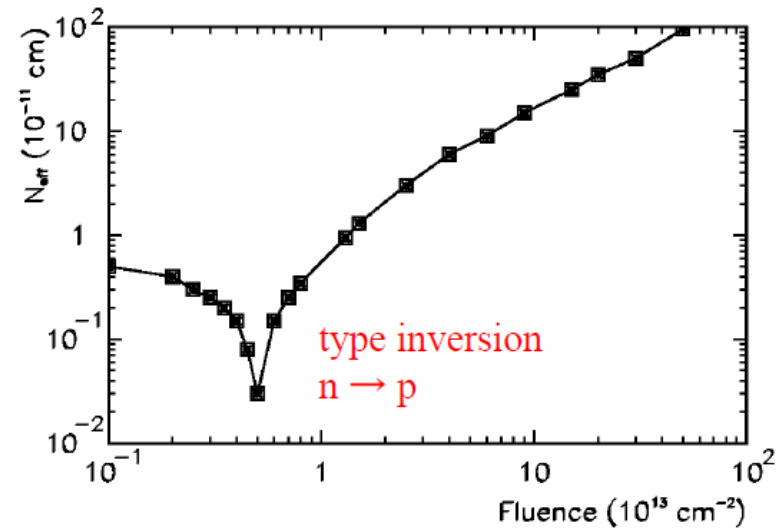


The advantage of P-bulk sensor

P-on-N sensor (present SCT)

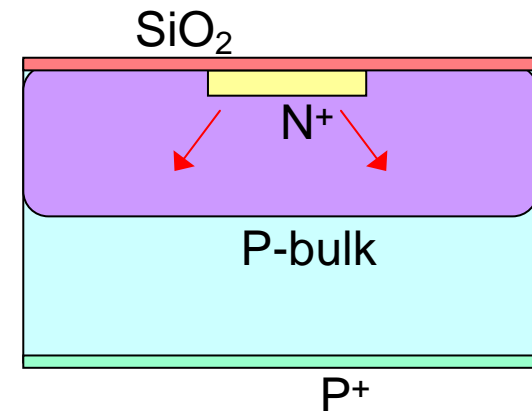


- Need to be fully depleted to read out signal.



N-on-P sensor

No Type inversion



- Signal can be read out even under partial depletion